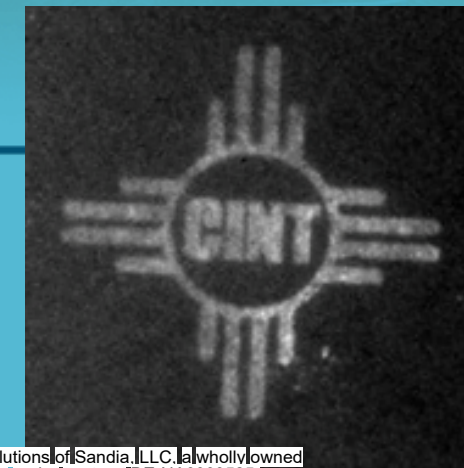




# Low-Energy Ion Implantation - Range Comparisons between Theory and Experiment

Michael Titze, Jonathan Poplawsky, Alex Belianinov, Edward Bielejec

11/10/2022



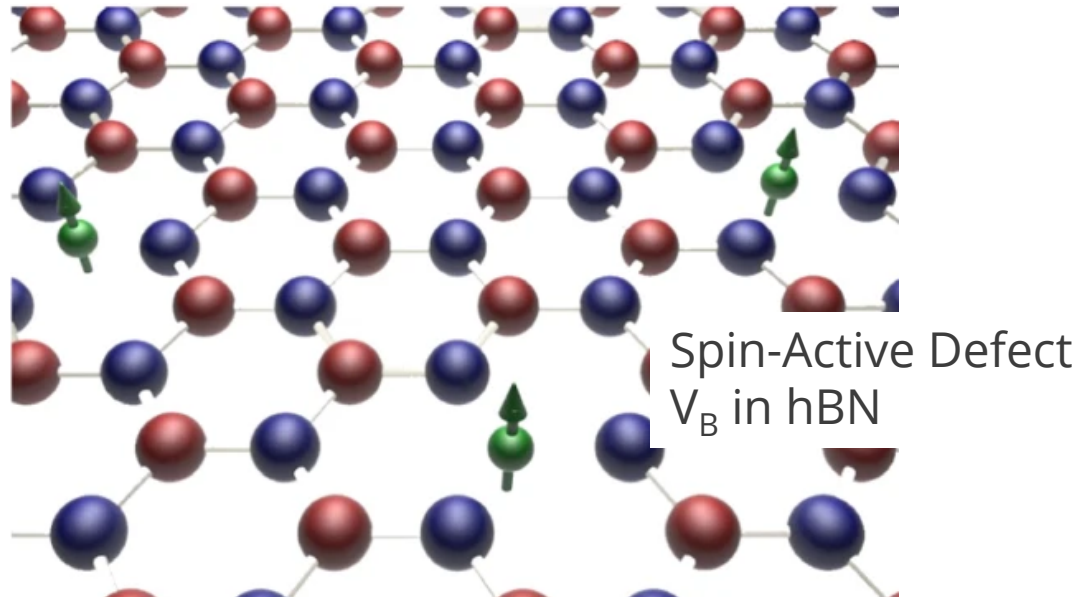
Sandia National Laboratories is a multimission laboratory managed and operated by National Technology & Engineering Solutions of Sandia, LLC, a wholly owned subsidiary of Honeywell International Inc., for the U.S. Department of Energy's National Nuclear Security Administration under contract DE-NA0003525.

SAND2022-10363 C

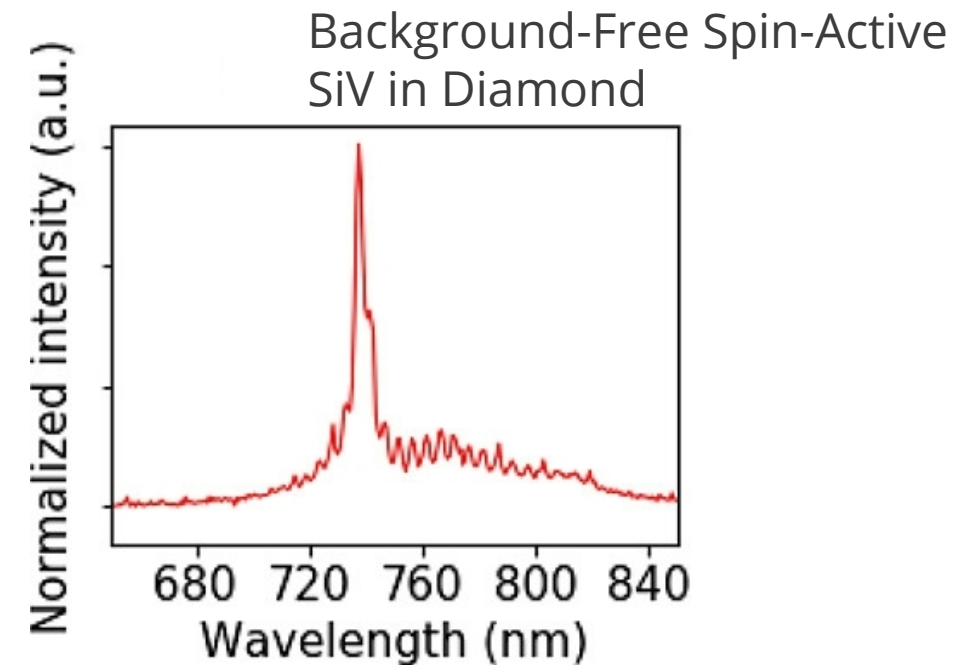
# Motivation for 2D Material Emitters



- 2D materials are attractive material class for CMOS-integrable quantum optics
- Deterministic placement of **impurity**-type emitters is challenging
  - Stopping in single atomic layer
  - Minimize damage to surrounding lattice
  - Introduce non-native atom



A. Gottscholl et al., Nat. Mater., 19, 540 (2020)

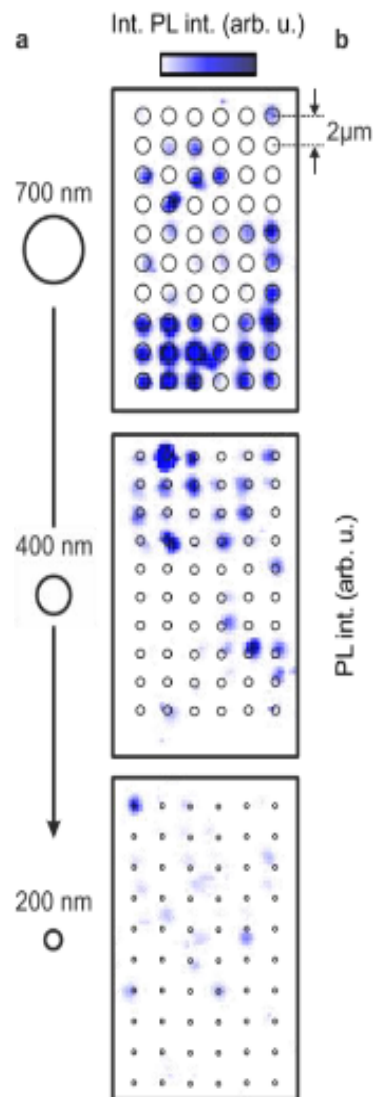


M. Titze et al., Nano Lett. (2022)

# How to make Defect Emitters in 2D Materials



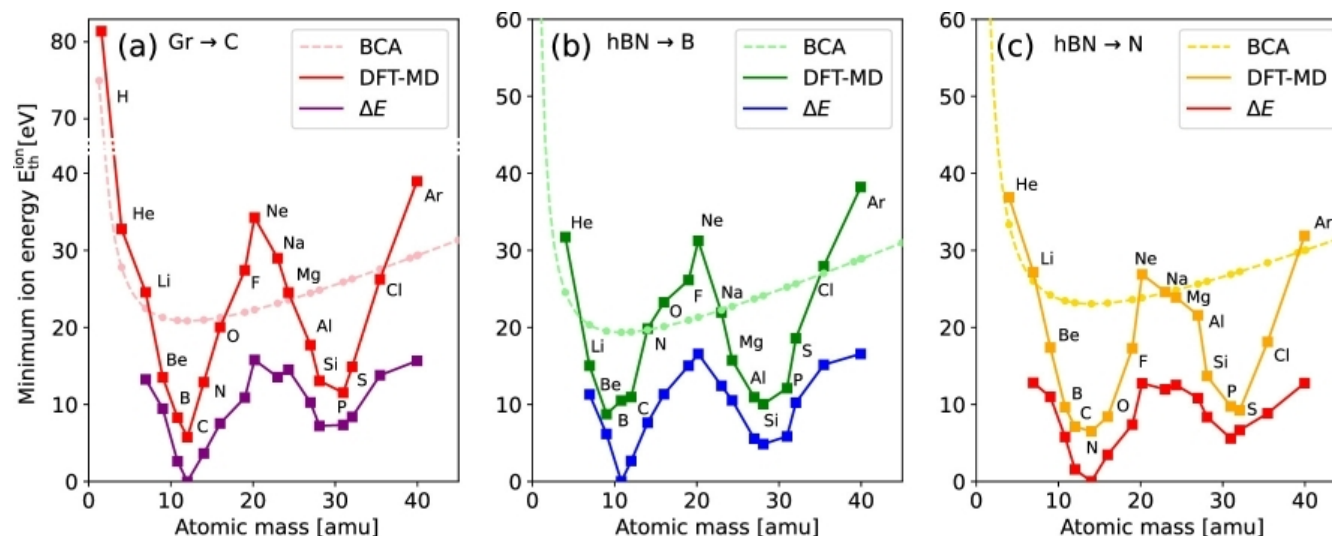
## Vacancy Defects



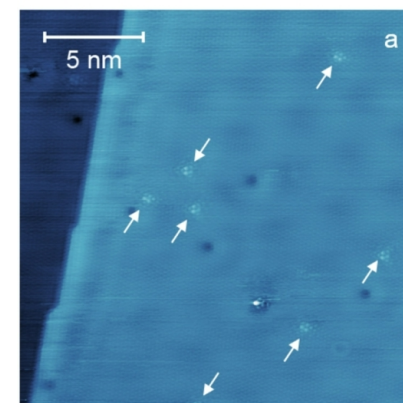
J. Klein et al., ACS  
Photonics, 8, 2, 669 (2021)

He Ion Microscope  
35 keV He @  $5 \times 10^{12}$   
ions/cm<sup>2</sup>

## Impurity Defects (Background Free Emitters)



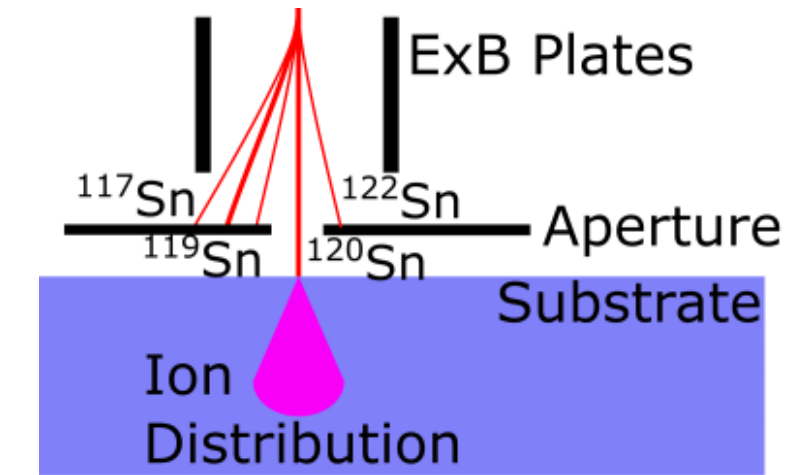
S. Kretschmer et al., J. Phys. Chem. Lett., 13, 2, 514 (2022)



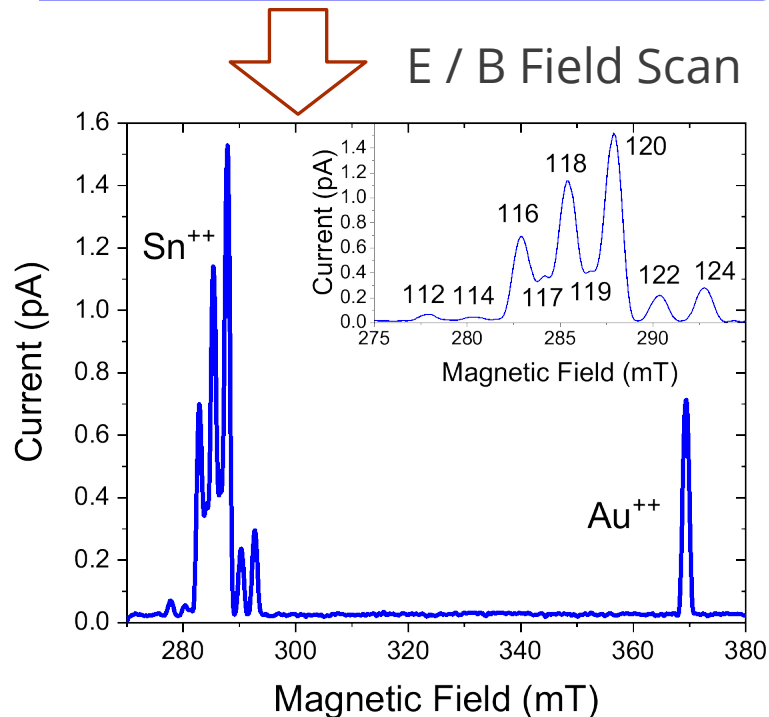
40 eV Mn in Graphene

P. C. Lin et al., ACS  
Nano, 15, 3, 5449 (2021)

# Impurity Implantation using Liquid Metal Alloy Ion Sources



Added 8 new elements over past 3 years



Green: Demonstrated at SNL

Purple: Attempting at SNL

Yellow: Demonstrated at other lab

1 H																	2 He				
3 Li	4 Be															5 B	6 C	7 N	8 O	9 F	10 Ne
11 Na	12 Mg															13 Al	14 Si	15 P	16 S	17 Cl	18 Ar
19 K	20 Ca	21 Sc	22 Ti	23 V	24 Cr	25 Mn	26 Fe	27 Co	28 Ni	29 Cu	30 Zn	31 Ga	32 Ge	33 As	34 Se	35 Br	36 Kr				
37 Rb	38 Sr	39 Y	40 Zr	41 Nb	42 Mo	43 Tc	44 Ru	45 Rh	46 Pd	47 Ag	48 Cd	49 In	50 Sn	51 Sb	52 Te	53 I	54 Xe				
55 Cs	56 Ba	57 La	*	72 Hf	73 Ta	74 W	75 Re	76 Os	77 Ir	78 Pt	79 Au	80 Hg	81 Tl	82 Pb	83 Bi	84 Po	85 At	86 Rn			
87 Fr	88 Ra	89 Ac	*	*	104 Rf	105 Db	106 Sg	107 Bh	108 Hs	109 Mt	110 Ds	111 Rg	112 Cn	113 Nh	114 Fl	115 Mc	116 Lv	117 Ts	118 Og		
			*	58 Ce	59 Pr	60 Nd	61 Pm	62 Sm	63 Eu	64 Gd	65 Tb	66 Dy	67 Ho	68 Er	69 Tm	70 Yb	71 Lu				
			*	*	90 Th	91 Pa	92 U	93 Np	94 Pu	95 Am	96 Cm	97 Bk	98 Cf	99 Es	100 Fm	101 Md	102 No	103 Lr			

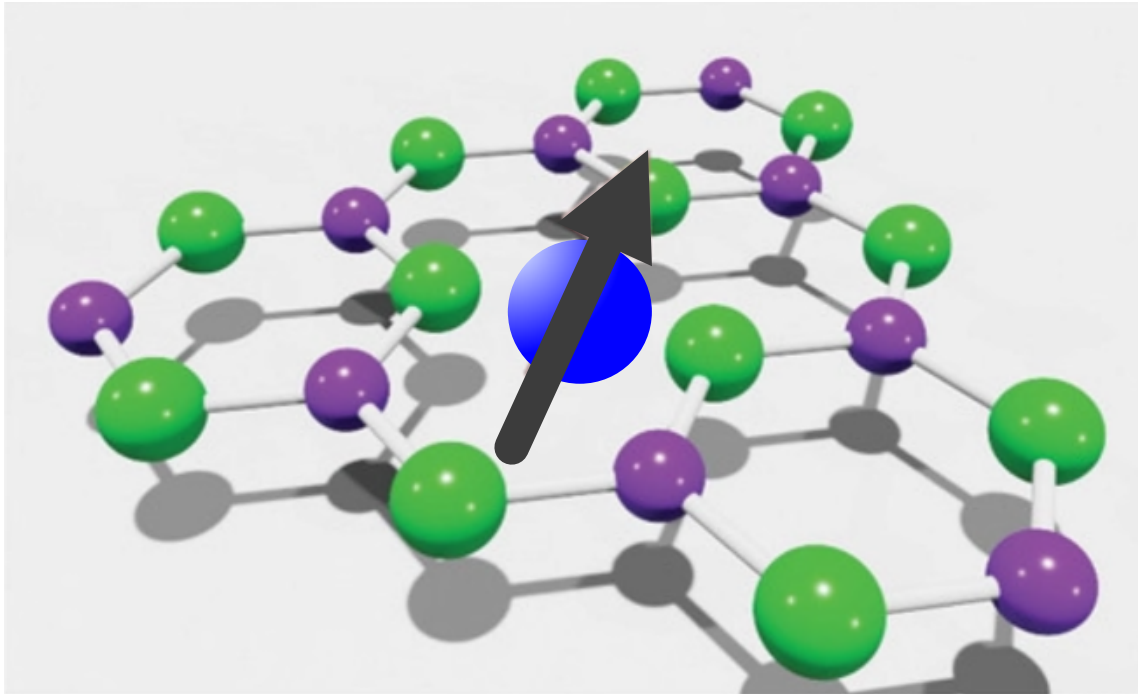
Green: Demonstrated at SNL

Purple: Attempting at SNL

Yellow: Demonstrated at other lab



# Challenges with FIB-Based Ultra-Low Energy Ion Implantation

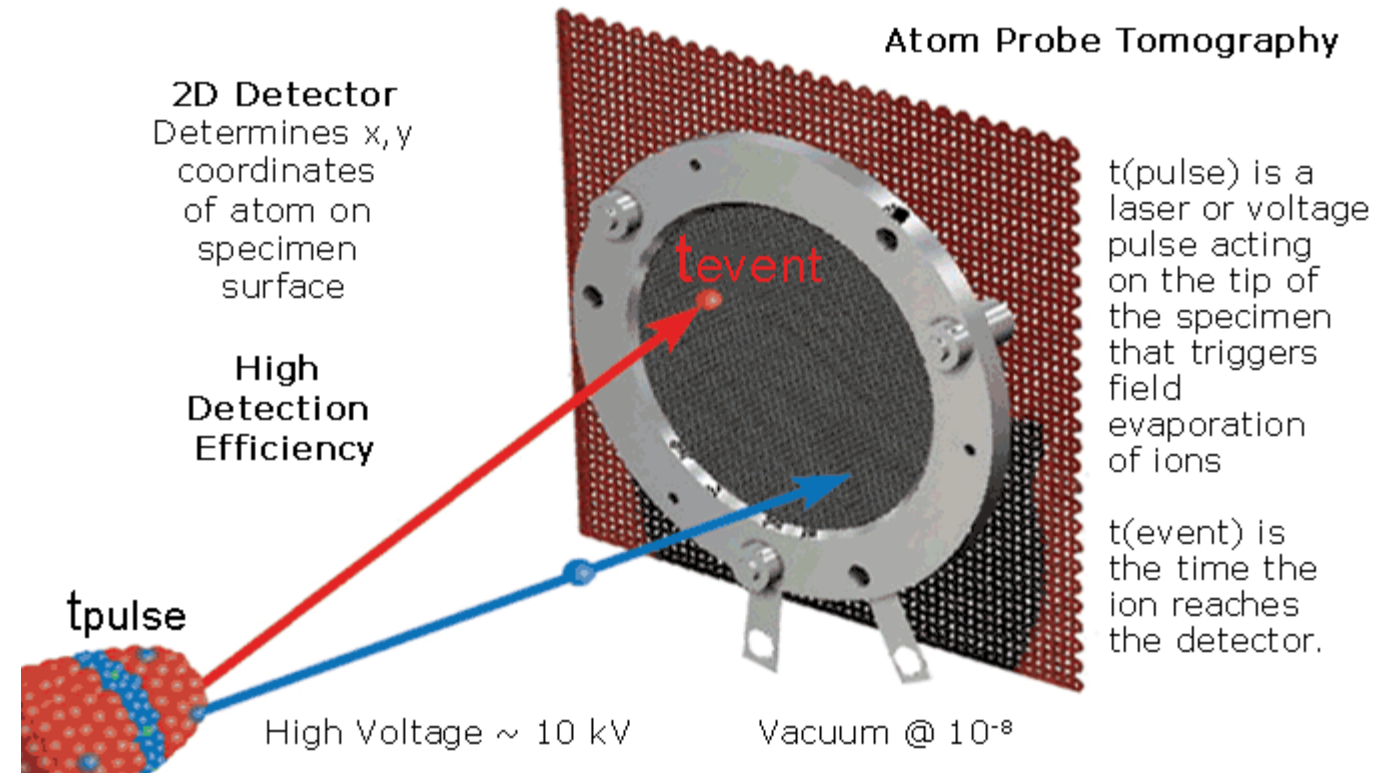


Adapted from N. Mendelson et al.,  
Adv. Mater., 34, 2106046 (2022)

- Spot Size increase due to chromatic aberrations → targeting 100-300 nm spatial resolution
- Range Prediction vs Experiment → SRIM overestimates range by 30% at 10 keV
- Need to reduce the implantation Energy to stop in atomic monolayer → This Talk!

# Atom-Probe Tomography as a probe for ultra-shallow implantation

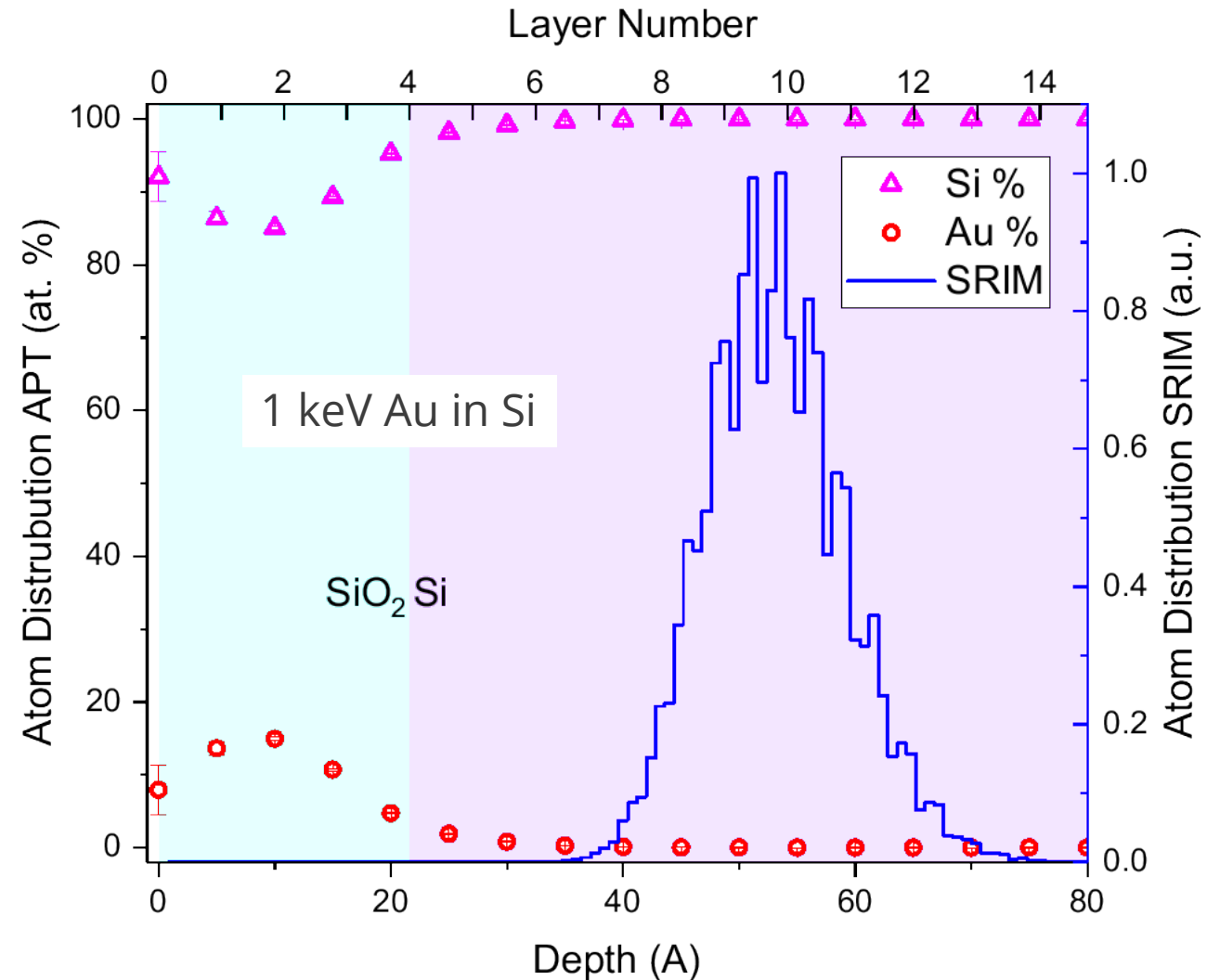
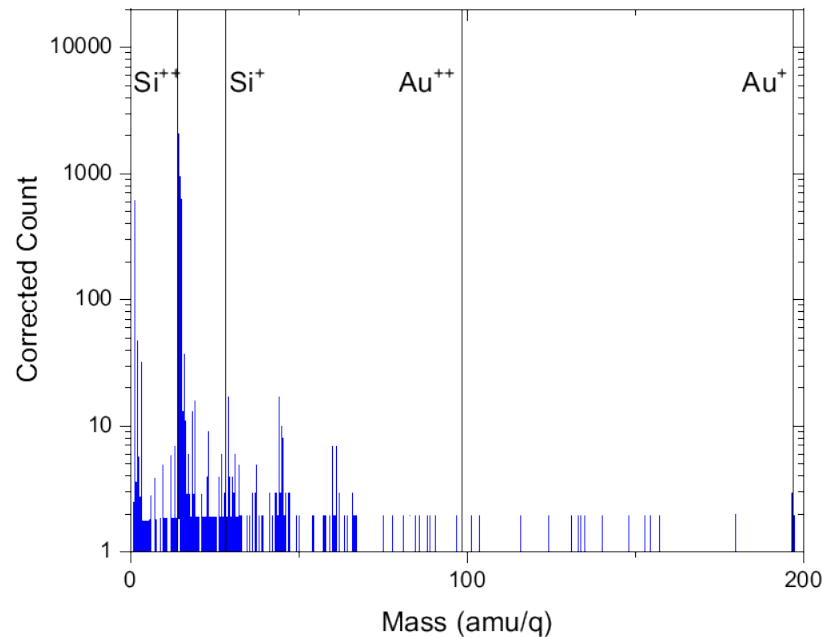
- Field emission from a sharp Si tip
- TOF mass spectroscopy by applying short voltage pulses
- Atomic layer resolution from calibration to Si lattice planes



# Atom-Probe Tomography on Low Energy Implanted Sample



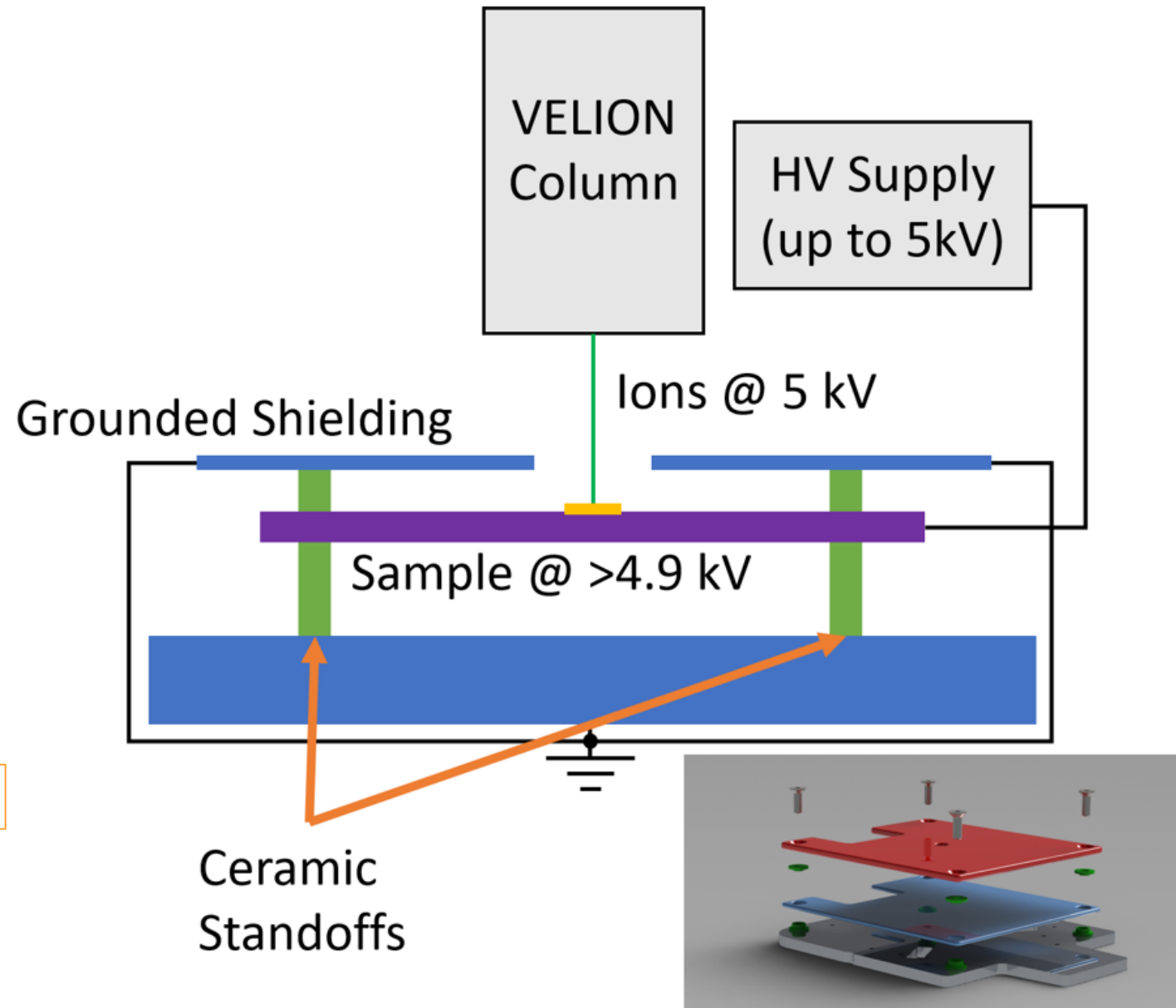
- SRIM overestimates range by **6X**
  - SRIM is not made for such low energy
- Indicates that 100s of eV will be sufficient to target single atomic layers



# How to further reduce the implantation energy?

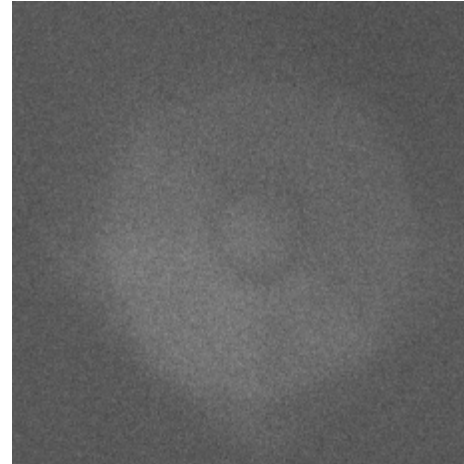
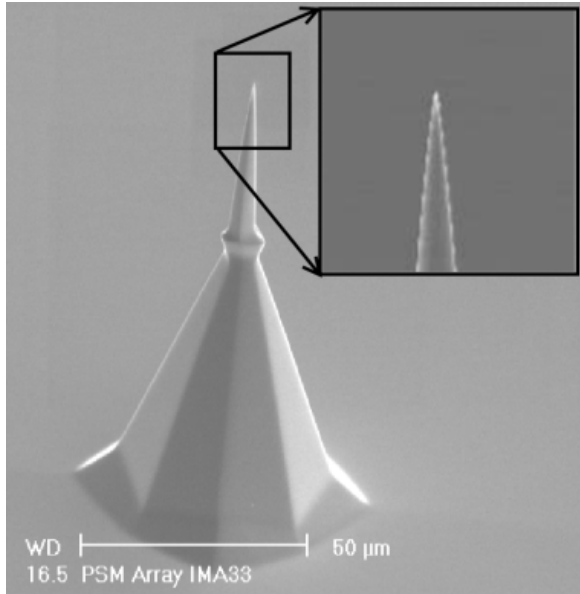
- 1 keV Au stops within 4 atomic layers of  $\text{SiO}_2$
  - To target atomic layers of 2D materials
    - Stopping in a single layer
    - Lower mass ions interesting for their optical properties
- Need even lower energy

Biased sample holder to decelerate ions

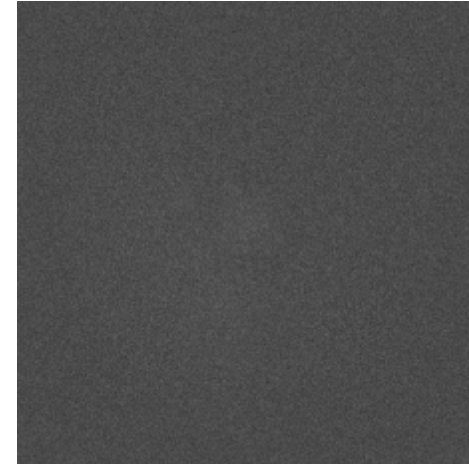




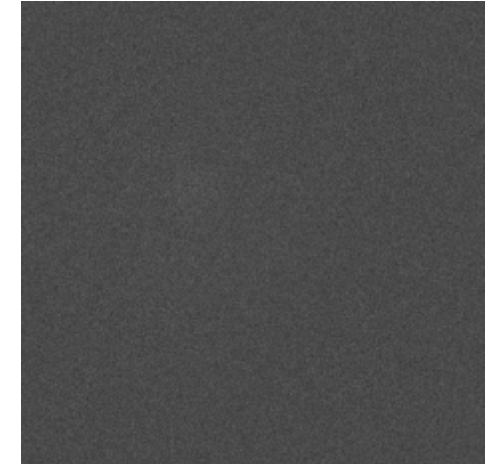
# Stimulated Emission Observed at Low Energy



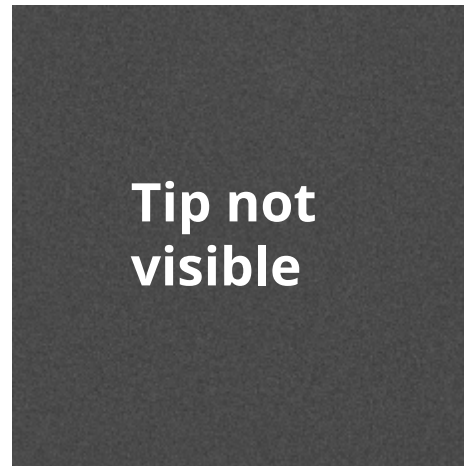
5 kV Au<sup>+</sup> HVPS Off



5 kV Au<sup>+</sup> HVPS 1kV

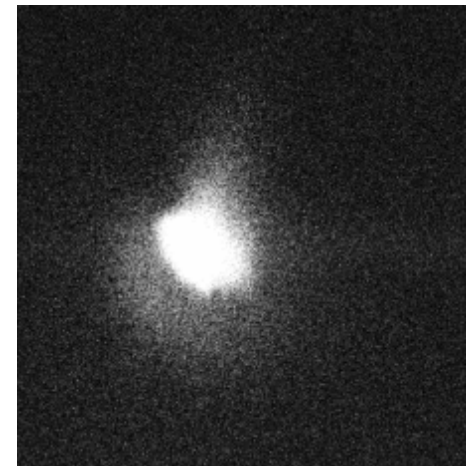


5 kV Au<sup>+</sup> HVPS 2kV



Tip not  
visible

5 kV Au<sup>+</sup> HVPS 4 kV



5 kV Au<sup>+</sup> HVPS 4.9 kV

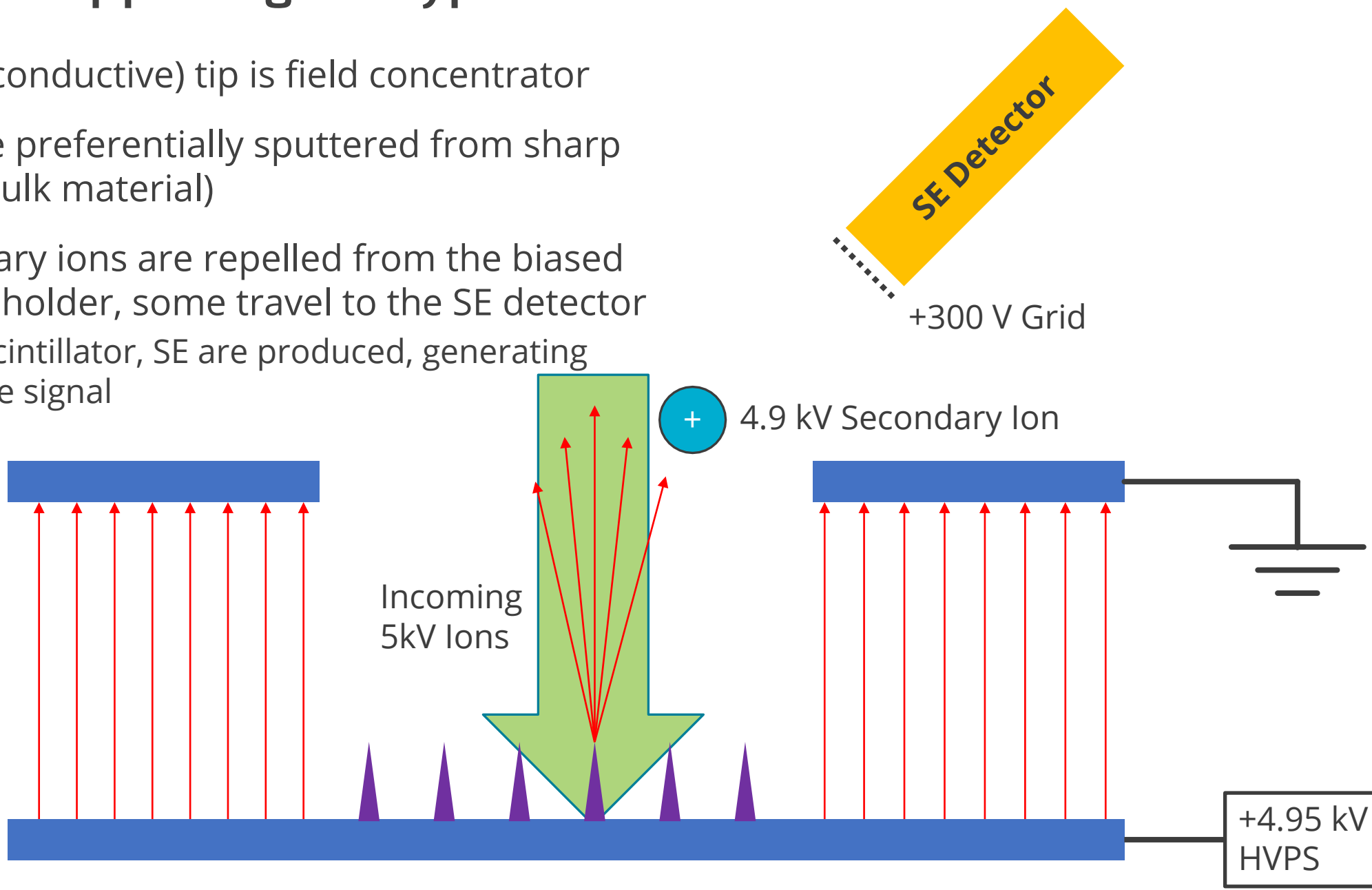


5 kV Au<sup>+</sup> HVPS 4.95kV

# What is Happening? – Hypothesis of Emission Mechanism

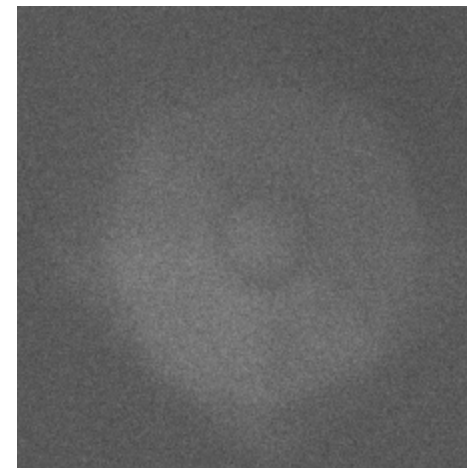
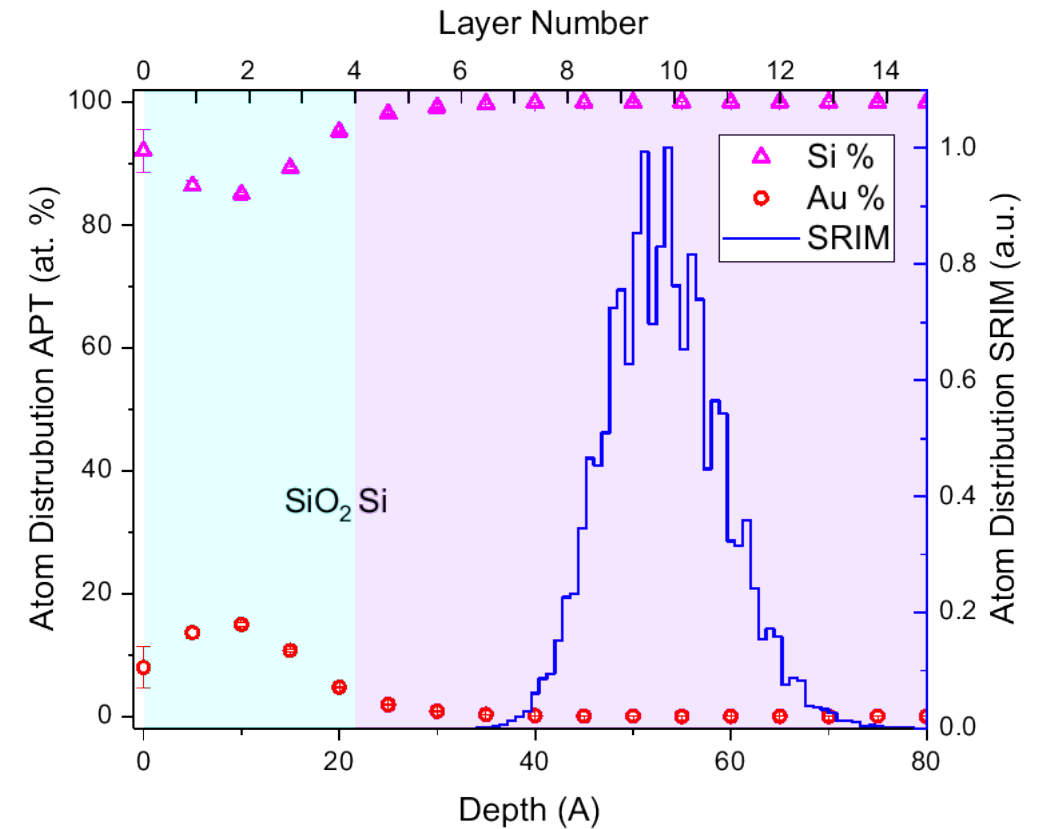


- Sharp (conductive) tip is field concentrator
- Ions are preferentially sputtered from sharp tip (vs bulk material)
- Secondary ions are repelled from the biased sample holder, some travel to the SE detector
  - In scintillator, SE are produced, generating large signal



# Conclusion

- Focused ion beam implantation down to 1 keV has been demonstrated
  - SRIM simulation does not work at low energies, need different modeling code
- Lower energy implantation has been done, sample is awaiting APT measurement
- At >4.8 kV sample bias stimulated emission is observed



5 kV Au<sup>+</sup> HVPS Off

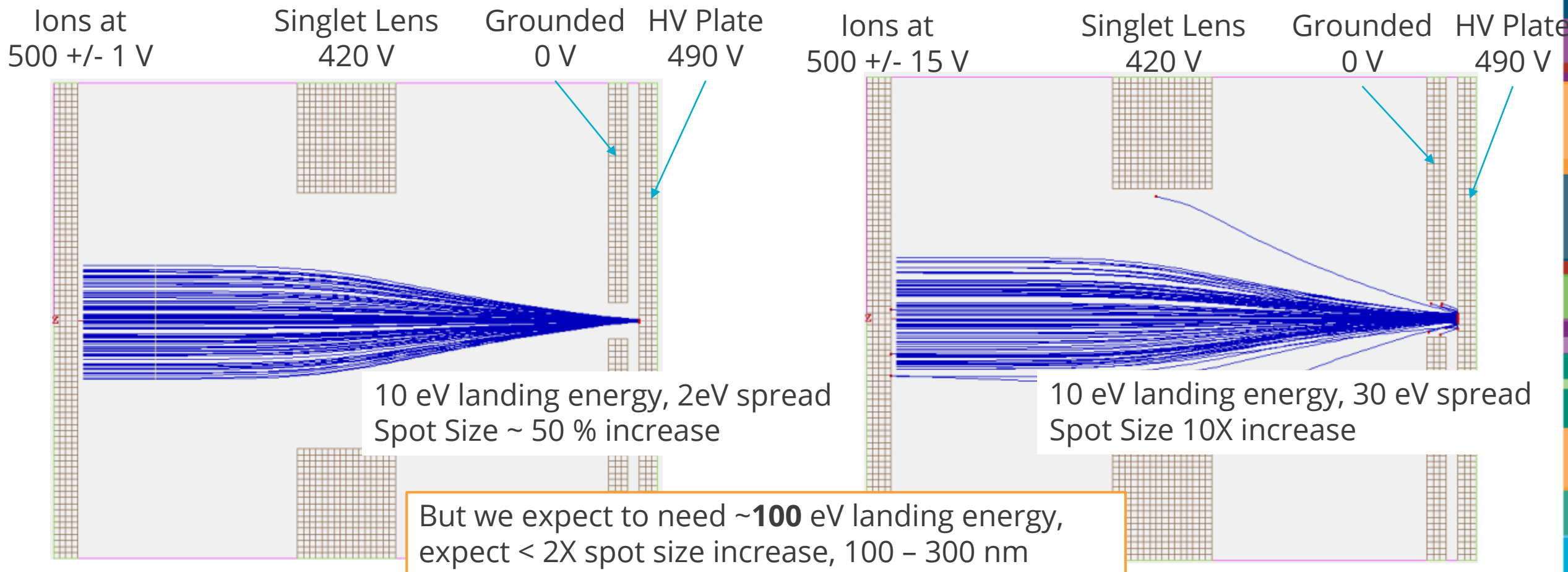


5 kV Au<sup>+</sup> HVPS 4.95kV

# Ion Source Energy Spread Disallows Focusing



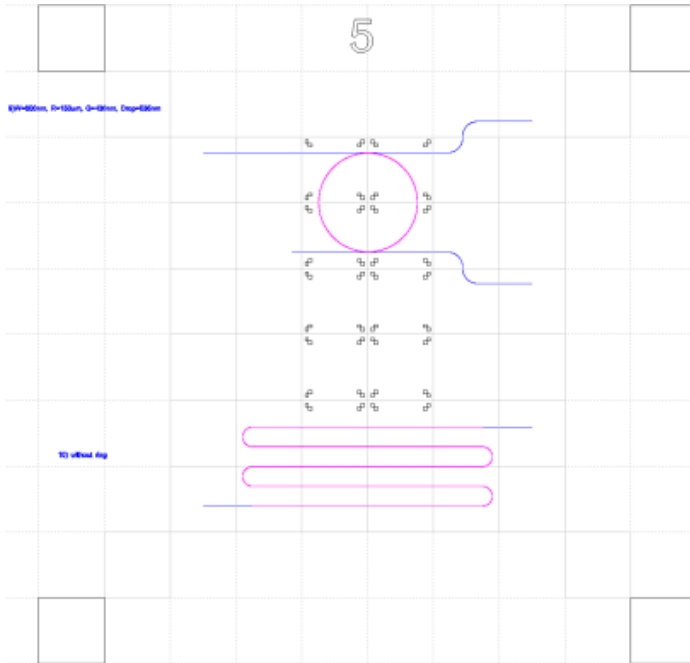
- SIMION Simulations show the ion deceleration leads to increased spot size
- When landing energy  $\sim$  energy spread ions get reflected + spot size increases



# Interaction with CINT Users – Design to Manuscript

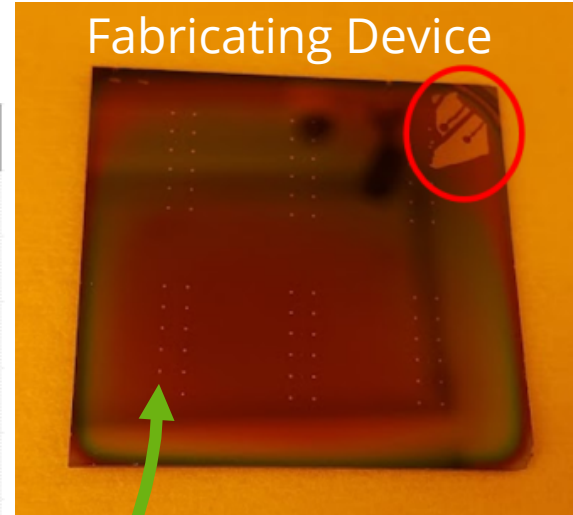


M. Hosseini @ Purdue

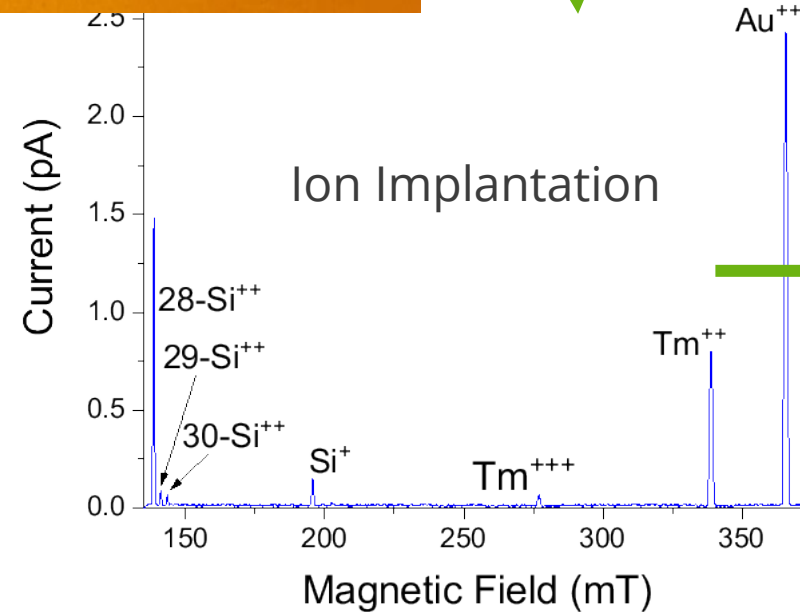


Discussion of design feasibility

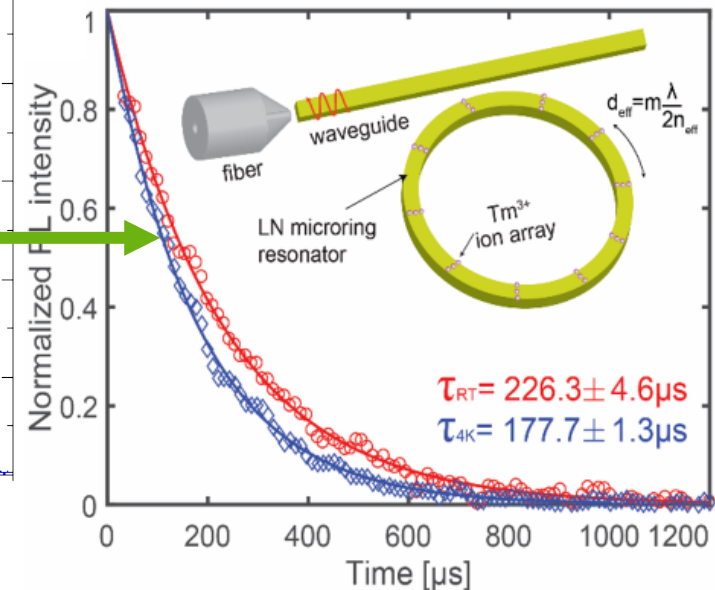
Fabricating Device



Tm for LiNbO<sub>3</sub>  
Photonics



Post-Processing  
+ Measurement





# How can YOU access these capabilities? CINT User Proposal





## THE CENTER FOR INTEGRATED NANOTECHNOLOGIES

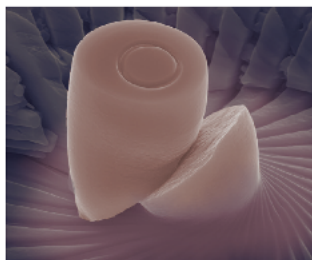


**One Scientific Community Focused on Nanoscience Integration**

The Center for Integrated Nanotechnologies (CINT) is a Department of Energy Office of Science Nanoscale Science Research Center. CINT offers world-leading scientific expertise and specialized capabilities to create, characterize, and integrate nanostructured materials at a range of length scales, from the nano- to meso-scale. It is jointly operated by Los Alamos and Sandia national laboratories and leverages the unmatched scientific and engineering expertise of the host labs.

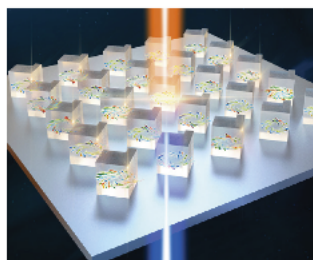
### Science Thrusts

Integration is the key to exploiting the novel properties of nanoscale materials and creating new technologies. CINT's scientific staff and capabilities are organized around four interdisciplinary science thrusts which address different challenges in nanoscience integration.



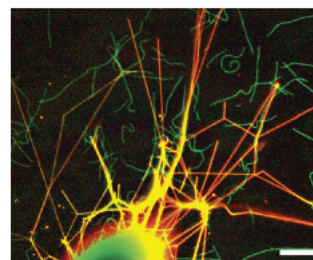
#### *In-Situ Characterization and Nanomechanics*

Developing and implementing world-leading capabilities to study the dynamic response of materials and nanosystems to mechanical, electrical, or other stimuli.



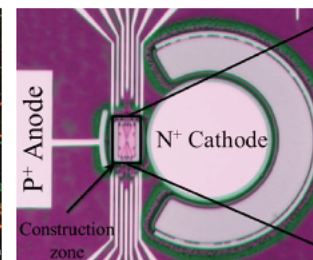
#### *Nanophotonics & Optical Nanomaterials*

Synthesis, excitation, and energy transformations of optically active nanomaterials and collective or emergent electromagnetic phenomena (plasmons, metamaterials, photonic lattices).



#### *Soft, Biological & Composite Nanomaterials*

Synthesis, assembly, and characterization of soft, biomolecular, and composite nanomaterials that display emergent functionality.



#### *Quantum Materials Systems*

Understanding and controlling quantum effects of nanoscale materials and their integration into systems spanning multiple length scales.

The Center for Integrated Nanotechnologies (CINT)

<https://cint.lanl.gov/>

### User Program

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